

Title: Operation of 10 deg beamline

Rev No: 0002
Issue Date: 31/10/2011

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Approved by: Jeroen van Kan

Review Date: 04/11/2011

1 Objective:

This Standard Operation Procedure states how to use 10 deg beam line for fabricating micro/nano structures on resists.

2 Responsibilities:

2.1 Director / HOD / PI

The Director/HOD/PI has overall responsibility for ensuring a process is designed for the safe to fabricate micro/nano structures at 10 deg beam line.

2.2 Designated Person

There shall be a designated person to oversee the correct procedures of fabrication micro/nano structures at 10 deg beam line.

2.3 Staff/ Research personnel

- a. Users shall attend appropriate training on the safe use of 10 deg beam line.
- b. Users shall report any injuries, defects or breakdowns to their supervisor.

3 Personal Protection Equipment

When handling samples during operation at 10 deg beam line requires special protection equipment including: rubber gloves.

4 Procedures

4.1. *Sample exchange in 10 deg chamber*

- 4.1.1. Press home on ion scan and switch off the X-Y-Z stage power supply.
- 4.1.2. Switch off the power supply for the CEM. Reduce RBS and or PIN bias to 0V.
- 4.1.3. Close the gate valve and the beam line valve to separate the sample chamber from the beam line and the accelerator and vent the chamber.
- 4.1.4. Take out the sample holder from the chamber.
- 4.1.5. **Wear gloves while handling samples and sample holder!**
- 4.1.6. Transfer the sample holder in the chamber.
- 4.1.7. Close the venting valve and start roughing the chamber.
- 4.1.8. Wait until the chamber pressure is lower than 2×10^{-1} mbar, close the roughing valve and open the gate valve to the TMP.

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4.1.9. Switch off the roughing-pump.

4.1.10. When the pressure in the sample chamber is lower than 2×10^{-5} mbar, the stage can be switched on.

4.2. Running experiment

4.2.1. **Switch on the stage and run the initialize stage programme.**

4.2.2. Bias your required detectors RBS < 20V, PIN = 10V, CEM extra Bias < 250V.

4.2.3. When using CEM keep the current below 1 pA

4.3. Shutting down process

~~4.2.4.~~4.3.1. Put in Faraday Cup 2.

~~4.2.5.~~4.3.2. Turn off Blanking Power Suppler and terminate connections.

~~4.2.6.~~4.3.3. Follow 4.1.1 – 4.1.4 and take out your sample.

~~4.2.7.~~4.3.4. Follow 4.1.7 – 4.1.10 and pump down the chamber

~~4.2.8.~~4.3.5. Close the 10 deg beam line valve